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D.BELL

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: SCHULTZ ET AL.  
Serial No: 09/627,559  
For: ILLUMINATION SYSTEM WITH A PLURALITY OF LIGHT SOURCES  
Filed: JULY 27, 2000  
Examiner: BERNARD E. SOUW  
Art Unit: 2881 Docket No.: 637.0003USU

AMENDMENT

Commissioner for Patents  
Washington, D.C. 20231

Dear Sir:

Applicants are submitting the present document in response to an Office Action dated June 27, 2002. Please amend the above-noted application as follows:

IN THE SPECIFICATION

Please amend the portions of the Specification identified below to read as indicated herein. A version of the amended portions of the Specification with markings to show changes made is included at the end of this document.

Page 3, paragraph starting at line 26✓

If the numerical aperture in the plane of the wafer is in the range  $NA_{\text{wafer}} = 0.1-0.25$  then in the case of 4:1 systems, a numerical aperture in the reticle plane of  $NA_{\text{reticle}} = 0.025$ -

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02 FC:1251 110.00 OP

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